Rear point contact structures for performance enhancement of semi-transparent ultrathin Cu(In,Ga)Se₂ solar cells

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ABSTRACT: Semi-transparent ultrathin Cu(In,Ga)Se₂ (CIGSe) solar cells offer many promising applications but their efficiencies are still limited. In this work, SiO₂ point contact structures were prepared using nanosphere lithography on Sn:In₂O₃ (ITO) substrate and ultrathin CIGSe solar cells were fabricated on top. It was discovered that the SiO₂ point contact structure at the CIGSe/ITO interface behaves significantly different from at the CIGSe/Mo interface and does not improve the rear interface reflectivity or short-circuit current density. However, the SiO₂ point contact structure brings pronounced electrical benefits, arising from the joint effect of reduced back recombination and induced field effect by internal charges. Semi-transparent ultrathin CIGSe solar cells with an absorber thickness of 380 nm exhibited a significant increase in open circuit voltage of 26 mV and fill factor of 9.4% (absolute). Consequently, the efficiency is improved by 23% (from absolute 6.8% to 8.4%).

KEYWORDS: point contact, back contact passivation, ultrathin CIGSe solar cells, transparent back contact, nanosphere lithography

1 Introduction
CuIn\textsubscript{1-x}Ga\textsubscript{x}Se\textsubscript{2} (CIGSe) solar cells have been attracting extensive attention in the photovoltaic market. Besides high record efficiencies [1,2], CIGSe solar cells are holding unique features of a remarkably short energy payback time, minimal consumption of high purity materials and great tolerance to the variations of working conditions, offering them a great potential to compete with the dominant crystalline Si solar cells on the market [3]. However, mass production is likely to impact the supply of element In and Ga and thus reduces the competitiveness of CIGSe solar cells [4,5]. Therefore, an ultrathin absorber (< 500 nm) can significantly reduce the consumption of high purity materials and related cost. Further, it relaxes the requirements for CIGSe absorber qualities since the diffusion lengths of minority carriers are much reduced [6]. Conventionally, Mo is used as back electrode materials. Apart from its conductivity and good adhesion with CIGSe, excellent thermal stability for CIGSe deposition and the formation of an ohmic contact with CIGSe absorbers make Mo a unique option as back contact for CIGSe solar cells. However, Mo has intrinsic opaque property and exhibits poor interface reflectivity at the rear CIGSe/Mo interface, limiting the exploration of advantages for ultrathin CIGSe solar cells. Alternatively, CIGSe solar cells can be deposited on transparent conductive oxides (TCOs) such as F:SnO\textsubscript{2} (FTO), Al:ZnO (AZO), Sn:In\textsubscript{2}O\textsubscript{3} (ITO) [7,8]. It has been reported that ultrathin CIGSe cells (with a sub-500 nm absorber thickness) on TCO back contact are able to achieve a comparable absorption to their thick counterparts via light trapping structures [9]. Additionally, the TCO back contacts permit the application of CIGSe solar cells in multi-junction configuration as top cell [10,11], bifacial solar cell [12], solar window and backwall configuration (back illumination) [13,14]. It has been extensively demonstrated that rear point-contact structures are able to passivate the CIGSe/Mo interface and improve the CIGSe/Mo interface reflectivity for optoelectronic enhancement of ultrathin CIGSe solar cells [15–19]. However, the work so far is merely on Mo-based ultrathin CIGSe solar cells. Considering the promising application of TCO-based ultrathin CIGSe solar cells, it will be meaningful to investigate whether the point contact structures are working efficiently for CIGSe solar cells on TCO.
In this work, we prepared periodically SiO$_2$ point contact structures on ITO back contact using nanosphere lithography method. It is experimentally discovered that the point contact structures are capable of passivating the rear CIGSe/ITO interface for performance enhancement of ultrathin CIGSe solar cells. Semi-transparent ultrathin CIGSe solar cells with a 380 nm thick absorber show an improvement of 26 mV in open-circuit voltage ($V_{oc}$) and of 9.4% in fill factor ($FF$), respectively. As a result, the SiO$_2$ point contact structures give rise to a relative efficiency enhancement by 23%.

2 Experiments and characterizations

2.1) Point contact structure preparation

We employ the method of nanosphere lithography [20,21] to fabricate point contact structures. Figure 1 depicts the flow of the fabrication process. Commercial polystyrene (PS) latex solution is first mixed with ethanol in 1:1 volume and dipped at air/water interface by using a curved glass pipette. A closely packed PS spheres form a monolayer on the water surface. ITO substrates are carefully submerged in the water and the PS monolayer is then transferred to ITO surface by sucking out water. Subsequently, the PS spheres are etched from original 900 nm down to 600 nm in diameter by O$_2$ plasma at a bias pressure of 0.2 mbar for 12 minutes. Subsequently, the reduced PS spheres can serve as a mask for direct thermal evaporation of a 50 nm thick SiO$_2$ layer. Finally, the ITO substrates are placed in toluene to lift off the reduced PS nanospheres and SiO$_2$ point contact structures then remain on the ITO substrates.

![Figure 1 Schematic illustration of preparation flow of SiO$_2$ point contact structures on ITO using nanosphere lithography](image)

2.2) Solar cell preparation and characterization

ITO substrates are sputtered with a thickness of 200 nm and a sheet resistance $<10$ ohm/sq. For solar cell completion, CIGSe absorbers are co-evaporated on ITO substrate via the so-called 3-stage process [22]. To avoid deteriorating ITO properties, a low substrate temperature of 450 °C is employed. Afterwards, a 50 nm CdS thin film
is deposited on top of CIGSe via chemical bath deposition for the formation of pn junction, which is followed by a sputtered 130 nm i-ZnO and a 240 nm ZnO:Al layer. For performance measurements, metal front contact grids (Ni/Al) are evaporated through a shadow mask and solar cells are mechanically divided and the area of a single cell is 0.5 cm$^2$.

For the observation of morphology of point contact structures and solar cells, scanning electron microscopy (SEM) is employed using the signal of back scattering electrons. Wavelength-dispersive X-ray fluorescence analysis (XRF) is used to accurately measure CIGSe absorber compositions and thicknesses. An overall Ga/(Ga+In) ratio of 0.38 as well as a Cu/(Ga+In) ratio of 0.88 is obtained. The absorbers have a thickness of 380 nm. For electrical characterization, the current density–voltage ($J-V$) curves are recorded under standard AM 1.5 illumination condition by a sun simulator and the external quantum efficiency (EQE) is measured from wavelength 300 nm to 1200 nm.

3 Results and discussion

![Image](image.png)

Figure 2 (a) SEM image of SiO$_2$ point contact structures on ITO substrate and (b) cross section of a complete CIGSe solar cell on the SiO$_2$ point contact structure

Figure 2(a) shows a representative SEM image of the SiO$_2$ point contact structure on ITO substrate fabricated using nanosphere lithography. The point contacts (holes in the image), corresponding to the remaining surface of ITO, take the location of the removed PS spheres and follow their hexagonal periodicity. The diameter of a single point
contact is approximately 400 nm, which indicates that as high as 82% area of the substrate is covered by the insulating SiO$_2$ layer, leaving only 18% of ITO surface as collection channel for holes. An interesting point here is that the diameter of a single point contact (400 nm) is less than a reduced PS sphere mask (600 nm). This phenomenon is arising from our specific preparation setup: the SiO$_2$ thermal evaporation source is at an oblique angle rather than perpendicular below the sample holder, indicating that the evaporated SiO$_2$ material can be deposited under the vertical shadow of the PS spheres. Via the rotation of the substrate holder, the reduced PS spheres can thus shadow a smaller area than their geometrical cross sections. It should be stressed here that nanosphere lithography is a promising technology for point contact fabrication. The technology does not require complicated or expensive equipments and the area can be easily scaled to industrial module size [20,23,24]. Additionally, this technology is applicable for a broad range of sizes of PS spheres from micrometer to nanometer, which offers great flexibility to tune the size and distance of neighboring point contacts with the assistance of O$_2$ plasma etching. This implies that nanosphere lithography can be potentially a universal method to prepare point contacts for various solar cells and other optoelectronic devices.

Figure 3 (a) $JV$ curves, (b) EQE and (c) $JV$ parameters compared between bare and passivated ultrathin CIGSe solar cells (averaged from 6 samples)
To investigate the influence of point contact structures on the optoelectronic properties of the CIGSe devices, ultrathin CIGSe solar cells with an absorber thickness of 380 nm were fabricated on top. Figure 2(b) shows the cross section of a complete solar cell, where the point contact structures can be observed at the rear interface of CIGSe/ITO and CIGSe absorber grains are closely stacked on top. Figure 3(a) compares the $JV$ curves of bare and passivated ultrathin CIGSe solar cells on ITO and the corresponding parameters are listed in Figure 3(c) (averaged from 6 samples). After passivation, both open-circuited voltage ($V_{oc}$) and fill factor ($FF$) achieve significant enhancement, from 484 to 510 mV and 51.3% to 60.7%, respectively. Short-circuit current density ($J_{sc}$) remains unchanged. Consequently, the SiO$_2$ point contact nanostructures overall contribute to a relative efficiency improvement by 23% (from 6.8% to 8.4%).

In our previous study on Mo substrate, the SiO$_2$ point contact structure is also able to bring obvious $J_{sc}$ enhancement [18], which is however not observed in the case on ITO substrate. EQE curves in Figure 3(b) confirm this: only slight modulation in the spectrum with a drop in the wavelength range of 500-650 nm and an increase in the range of 650-800 nm. As a result, no $J_{sc}$ gain is obtained. Two reasons are assumed to be responsible for this phenomenon: firstly, the effective doping of absorbers for our ultrathin CIGSe solar cells on ITO is only in the order of $10^{15}$ cm$^{-3}$ (obtained from capacitance-voltage measurement, not shown here), which is one order of magnitude lower than the corresponding value on Mo. This indicates that the space charge region is wide enough, overlaps with the back contact and thereby carrier collection is already optimum in the short-circuit state. Additionally, $J_{sc}$ increase for ultrathin CIGSe solar cells with dielectric point contact structures on Mo substrate is mainly stemming from the absorption enhancement due to improved CIGSe/Mo interface reflectivity [15–18]. However, ITO exhibits different optical properties from Mo, and inserting a SiO$_2$ layer cannot improve the interface reflectivity of CIGSe/ITO. Since the SiO$_2$ point contact structures cover an area as high as 82% and are too thin (50 nm thick) to excite nano-optical effects [25], we assumed a planar SiO$_2$ layer at the rear interface and simulated absorption of the CIGSe layer ($\text{Abs}_{\text{CIGSe}}$) of CIGSe cells on (a) ITO and (b) Mo using transfer matrix method in Figure 4, respectively. The thicknesses of each layer were
chosen according to the experimental samples. Optical constants of each layer are from Ref. [26,27] and may pose certain differences from experimental samples, interface roughness is also not considered. It can be observed from Figure 4(a) that a 50 nm thick SiO₂ layer only causes slight modulation of Fabry–Pérot interferences on ITO substrate, which follows the changing trend of experimental EQE data in Figure 3(b). Noticeably, solar cells on Mo (Figure 4(b)) exhibit pronounced and broadband absorption enhancement in the long wavelength region after introducing the thin SiO₂ layer, which poses a sharp contrast to the case on ITO.

Figure 4 Effects of a SiO₂ layer on absorption in CIGSe \( \text{Abs}_{\text{CIGSe}} \) on (a) ITO and (b) Mo substrate.

It was widely demonstrated for ultrathin CIGSe solar cells on Mo that a dielectric point contact structure is capable of enhancing cell performance by interface defect passivation and an internal charge-induced field at the rear interface [17,28,29]. However, CIGSe solar cells on ITO typically have a potential barrier and form a Schottky contact because of the mismatch of work function between CIGSe and ITO [13,30], which is different from the cells on Mo with an Ohmic contact. To verify that the point contact structures are able to improve the performance of solar cells with a Schottky back barrier and that the experimental enhancement in electrical properties is arising from the SiO₂ point contact structure, we employ SCAPS [31] for theoretical study. The CIGSe absorber parameters were set according to experimental samples with a thickness of 380 nm, an effective doping of \( 4 \times 10^{15} \) cm\(^{-3} \), a lifetime of 5 ns and a bandgap of 1.2 eV, other parameters can be found in the supporting information. Due to the general complexity in electrical properties of CIGSe solar cells, the simulation
results here seek for simply explaining the experimental phenomenon rather than to produce exact value match. Figure 5 plots the $V_{oc}$, $J_{sc}$ and FF variations as a function of back recombination rate and back barrier potential. The recombination rate is varied in the range of $10^2$ to $10^6$ cm/s since most reported values are in this range [15,17,32]. A back barrier potential $\leq 0.2$ eV is typically assumed to be an Ohmic contact [33,34] and a value larger than 0.5 eV will lead to a very poor performance and does not reflect experimental results well, 0.2-0.5 eV was therefore set as the investigated range for back barrier potential. A bandgap diagram of CIGSe/ITO interface is shown in Figure 5(a). In Figure 5(b) it can be seen that as the back barrier potential is rising, $V_{oc}$ is deteriorating for a fixed recombination rate. This is due to the back barrier potential blocking the collection of holes. Experimentally, a back barrier potential $\geq 0.3$ eV is expected for our solar cells on ITO [9], $V_{oc}$ is thus poor ($< 0.6$ eV) and much lower than the corresponding value on Mo (not shown here). Additionally, $V_{oc}$ shows a general increasing trend as the recombination rate is reduced at a fixed back barrier potential. This improvement reflects our experimental observation above as well as other published results for the case on Mo with an Ohmic back contact when the point contact structures are introduced.

Figure 5(c) shows that the $J_{sc}$ value is relatively stable in the broad range of recombination rate $\leq 10^5$ cm/s and barrier potential $\leq 0.4$ eV. Since the CIGSe thickness is only 380 nm and the entire absorber is therefore within the space charge region, the collection of photogenerated carriers can be guaranteed and thereby $J_{sc}$ is less dependent on recombination rate and barrier potential. This further implies our experimental results where $J_{sc}$ is stable after integrating the point contact passivation structure.
Figure 5 (a) Sketch of bandgap diagram at CIGSe/ITO rear interface, (b) $V_{oc}$, (c) $J_{sc}$ and (d) $FF$ variation as a function of rear recombination rate and back barrier potential.

Furthermore, Figure 5(d) depicts that the $FF$ reaches the maximum value when the recombination rate is in the order of $10^4$ cm/s rather than improving further as the recombination rate becomes smaller. This implies that a reduction of recombination rate may be positive to avoid photo current losses but it is negative in terms of majority carrier (hole) flow. This is why $FF$ increases first and then reduces for cells with a Schottky contact, which indicates that further reducing point area (a lower recombination rate) is possibly harmful to $FF$ for cells on ITO, which is a sharp difference from solar cells on Mo with an Ohmic back contact.

Besides reduced recombination rate, it was proved that the point contact structures could contain negative internal charges and form a potential for repelling the electron flow towards the back contact [35,36], which benefits electrical properties of solar cells as well. Considering the significant improvement of $FF$ (9.4% absolute) in our experiment, it is quite likely that the $FF$ improvement after integrating the SiO$_2$ point contact structure is the joint result of reduced interface recombination rate and field effect of internal charges.
4 Conclusion and outlook

In this work, we investigated the optoelectronic effects of SiO$_2$ point contact structures on semi-transparent ultrathin CIGSe solar cells. Compared to the case on Mo [18], the SiO$_2$ point contact structures at the rear interface are not able to improve the interface reflectivity or $J_{sc}$ for ultrathin CIGSe solar cells on ITO. However, the point contact structures give rise to a $V_{oc}$ increase of 26 mV and a $FF$ increase of 9.4% absolute. Thanks to the improvement in electrical properties, ultrathin CIGSe solar cells with a 380 nm thick absorber exhibit an absolute efficiency enhancement of 1.6% (23% relative) after integrating the SiO$_2$ point contact structures. As the simulations indicated, the reduced rear interface recombination from the point contact structure contributes to the improvement of electrical benefits of ultrathin CIGSe solar cells on ITO with a back barrier.

To further explore the advantages of semi-transparent ultrathin CIGSe solar cells, the next steps are to a) further optimize the geometry and internal charge situation of point contact structures for a greater passivation effect and b) combine point contact structures with hole transporting layers for simultaneously solving the issues of back recombination and non-Ohmic back contact.

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